

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION OF

HONG et al.

Appln. No.: 09/886,984

Filed: June 23, 2001

Title: METHOD FOR FORMING A PHASE-SHIFTING MASK FOR SEMICONDUCTOR
DEVICE MANUFACTURE



Group Art Unit: 1756

Examiner:

#36
UEAR

September 18, 2001

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PRELIMINARY AMENDMENT

Hon. Commissioner of Patents
Washington, D.C. 20231

Sir:

Further to the application filing of June 23, 2001, please enter the following preliminary amendment.

IN THE CLAIMS:

Please enter the following amended claim 7:

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7. (Amended) A method for forming a multi-transmittance photomask on a transparent substrate according to claim 5, further comprising the step of forming an etch barrier layer on the second light blocking layer before forming the third light blocking layer.

See the attached Appendix for the changes made to effect the above claim(s).